## **AMENDMENTS TO THE SPECIFICATION:**

The paragraph beginning on page 13, line 23 has been changed as follows:

Fig. 10 shows a leakage current density obtained by reducing the TiCl<sub>4</sub> feeding time. According to Fig. 10, the TiCl<sub>4</sub> feeding time is reduced from about 1 second to about 0.15 seconds. At this time, the TiCl<sub>4</sub> flow rate is approximately 50sccm, and the NH<sub>3</sub> flow rate and feeding time are about 1000 sccm and 0.45 seconds, respectively. Also, during the first and second purge processes, an argon (Ar) flow rate and feeding rate are about 800sccm and 0.15 seconds, respectively. The deposition temperature is maintained constantly at about 470 [ $\Box$ ]  $\underline{\mathbb{C}}$ .